
**Surface chemical analysis — Depth
profiling — Method for sputter rate
determination in X-ray photoelectron
spectroscopy, Auger electron
spectroscopy and secondary-ion mass
spectrometry sputter depth profiling
using single and multi-layer thin films**

*Analyse chimique des surfaces — Profilage d'épaisseur — Méthode
pour la détermination de la vitesse de pulvérisation lors du profilage
d'épaisseur par pulvérisation en spectroscopie de photoélectrons par
rayons X, spectroscopie d'électrons Auger et spectrométrie de masse
des ions secondaires à l'aide de films minces multicouches*





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